

ABSTRACT

In the photomask blank 100, which is an original plate of a transfer mask having a transfer pattern to be transferred to the body to be subjected to transfer on the substrate 10, the photomask blank 100 includes a light shielding film 20 becoming the transfer pattern and a resist film 30 on the substrate 10, and the resist film 30 formed on the peripheral edge of the main surface of the substrate 10 is removed in a predetermined region in a supported region 31 of the photomask blank 100 supported by the substrate holding member of the exposure device, so that a desired pattern positional accuracy and a desired focus accuracy are obtained, when the transfer mask having the transfer pattern obtained by patterning the light shielding film 20 is supported by the substrate holding member of the exposure device. With this structure, when a reticle is mounted on the substrate holding member of a stepper, the deformation of the reticle is suppressed, and lowering of a positional accuracy of the transfer pattern and the lowering of a focus accuracy can be suppressed to minimum.